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(71) Applicant (for all designated States except US): MEMS DNS TECH CO., LTD. [KR/KR]; 85-3 Poongdukcheon-dong, Yongin-shi, Kyunggi-do 449-170 (KR).

(72) Inventor; and

(75) Inventor/Applicant (for US only): MIN, Dong-Hoon [KR/KR]; 408 Dongsak-dong, Pyungtak, Kyunggi-do 450-802 (KR).

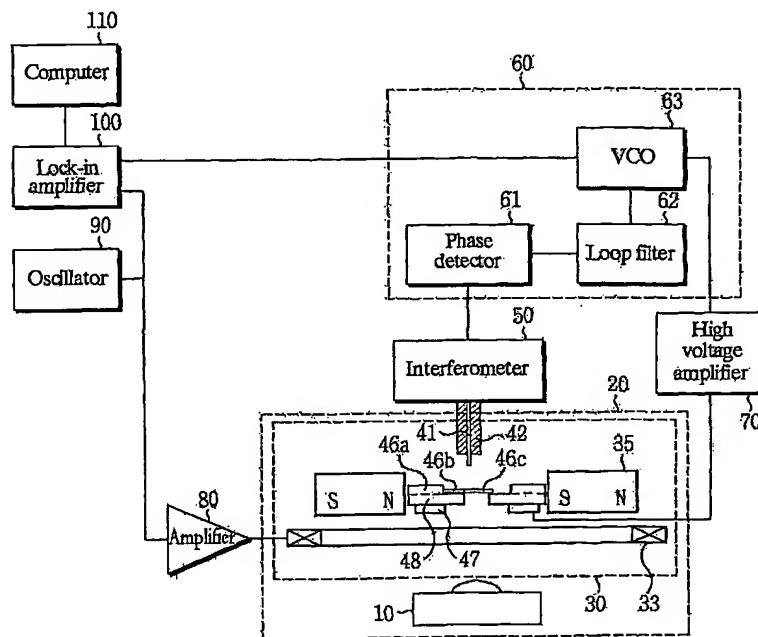
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(54) Title: ULTRA SENSITIVE IN-SITU MAGNETOMETER SYSTEM



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(57) Abstract: The present invention relates to an ultra sensitive in-situ magnetometer system, and more particularly to an ultra sensitive in-situ magnetometer system that can in-situ monitor a magnetic moment of a magnetic thin film with sub-monolayer precision while depositing and growing the magnetic thin film in an ultra high vacuum (UHV) chamber.



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